Amendments to the Claims

This listing of claims will replace all prior versions and listings of claims in the above-identified application.

Listing of Claims

1. (Amended) A method comprising:

forming a tungsten plug in a dielectric layer;

forming an electrically conductive interconnect line on the dielectric layer after formation of the tungsten plug, wherein the tungsten plug is electrically connected to the electrically conductive interconnect line;

introducing a gas into a liquid;

- discharging the tungsten plug by contacting the electrically conductive interconnect line with the gas introduced liquid after formation of the electrically conductive interconnect line;
- contacting the electrically conductive interconnect line with a solution to remove residual polymer after the electrically conductive interconnect line is contacted with the gas introduced liquid.
- 2. (Original) The method of claim 1 wherein the gas comprises carbon dioxide.
- 3. (Original) The method of claim 1 wherein the pH of the liquid is reduced by introducing the gas into it.
- 4. (Original) The method of claim 1 wherein the gas introduced liquid has a pH that is less than neutral.
- 5. (Original) The method of claim 4 wherein the pH of the gas introduced liquid is greater than 3.

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- 6. (Original) The method of claim 1 wherein the liquid is made more electrolytic by introducing the gas into it.
 - 7. (Original) The method of claim 1 wherein the liquid comprises water.
- 8. (Original) The method of claim 7 wherein the liquid is deionized before the gas is introduced into it.
 - 9. (Cancelled)
- 10. (Original) The method of claim 1 wherein contacting the electrically conductive interconnect line with the gas introduced liquid comprises spraying the electrically conductive interconnect line with the gas introduced liquid.
 - 11. (Currently Amended) The method of claim 1 A method comprising: forming a tungsten plug in a dielectric layer;
 - forming an electrically conductive interconnect line on the dielectric layer after formation

 of the tungsten plug, wherein the tungsten plug is electrically connected to the

 electrically conductive interconnect line;

introducing a gas into a liquid;

discharging the tungsten plug by contacting the electrically conductive interconnect line

with the gas introduced liquid after formation of the electrically conductive

interconnect line;

wherein introducing the gas into the liquid further comprises:

the gas flowing into a first chamber;

the liquid flowing into a second chamber, wherein the first and second chambers are separated by a porous membrane;

the gas flowing into the first chamber passing into the second chamber via the porous membrane and dissolving into the liquid in the second chamber.

12. - 20 (Withdrawn)

- 21. (New) The method of claim 11 wherein the gas comprises carbon dioxide.
- 22. (New) The method of claim 11 wherein the gas introduced liquid has a pH that is less than neutral.
- 23. (New) The method of claim 22 wherein the pH of the gas introduced liquid is greater than 3.
 - 24. (New) The method of claim 11 wherein the liquid comprises water.

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